

PHOTORESISTIVE COMPOSITION

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Inventor: NAKAI HIDEYUKI; GOTO SEI; TOMIYASU HIROSHI;
KOBAYASHI YOSHIKO
Applicant: KONISHIROKU PHOTO IND.; MITSUBISHI CHEM IND
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Abstract of JP2096755

PURPOSE: To obtain a photosensitive compsn. having superior capacity for forming visible picture by exposure, as well as superior under developability and high sensitivity by constituting the compsn. of 1,2-naphthoquinone-2-diazide-4-sulfonic ester compd. an alkali soluble resin, a halomethyl oxadiazole compd., as a discoloring agent. **CONSTITUTION:** The title compsn. contains 1,2-naphthoquinone-2-diazide-4-sulfonic ester compd., the alkali-soluble resin, the halomethyl oxadiazole compd. which generates free halogen radicals by irradiating with active light rays, and a discoloring agent which changes its tone by the interaction with a photolysis of the halomethyl oxadiazole compd. Suitable alkali-soluble resin is particularly novolak resin and vinyl polymer having structure units having phenolic OH groups in the molecule. A photosensitive planographic printing plate having superior capacity for forming visible picture by exposure, superior under developability, as well as high sensitivity, is obtd. from the above-described compsn.

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